

ABSTRACT

5 A reflective photomask blank including a substrate, a multilayer reflection film, a
protection film and a light absorbing film that has a phase shift function is provided. The
light absorbing film contains ruthenium and chromium and is free of oxygen and nitrogen,
and has a ruthenium content of 5 to 15 at%, a chromium content of 85 to 95 at%, a
thickness of 40 to 56 nm, and a reflectance of 2 to 5% and a phase shift of 200 to 230
10 degrees with respect to exposure light being light in extreme ultraviolet range.

[Figure 1]